

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8	@rlad<"20001220" and simulat\$3 and tri-tone and (phase-shift\$3 or (phase adj shift\$3)) and (opc or (optical adj proximity adj correction)) and (mask or layout)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 15:50
L10	1	"6503666".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 09:45
L11	29	09/130996	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 09:46
L13	8	@rlad<"20001220" and simulat\$3 and tri-tone and (opc or (optical adj proximity adj correction))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:05
L14	1	"5682323".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:06
L15	258	@rlad<"20001220" and simulat\$3 and (opc or (optical adj proximity adj correction) and ((rim with width) or (phase adj shift\$3)))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:36
L16	16	@rlad<"20001220" and simulat\$3 and (opc or (optical adj proximity adj correction)) and (rim and (phase adj shift\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:09
L17	8	@rlad<"20001220" and tri-tone and (phase with shift\$3) and (layout or mask) and (opc or (optical adj proximity adj correction) and rim)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:28
L18	8	15 and (tri-tone or (tri adj tone) or tritone)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:34

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L19	253	@rlad<"20001220" and simulat\$3 and (opc or (optical adj proximity adj correction) and ((rim with width) and (phase adj shift\$3)))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:36
L20	10	@rlad<"20001220" and simulat\$3 and tri-tone	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 15:27
L21	19	@rlad<"20001220" and simulat\$3 and (tri-tone or (tri adj tone) or tritone)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:54
L22	12	@rlad<"20001220" and simulat\$3 and (tri-tone or (tri adj tone) or tritone) and (mask or layout)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:54
L23	0	@rlad<"20001220" and simulat\$3 and tri-tone and (opc or (optical adj proximity adj correction)) and (mask or layout) and (rim with width)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 15:51
L24	0	@rlad<"20001220" and simulat\$3 and tri-tone and (opc or (optical adj proximity adj correction)) and (mask or layout) and rim	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 15:51
L25	38	@rlad<"20001220" and simulat\$3 and (attenuat\$3 with phase-shift\$3 with mask) and (opc or (optical adj proximity adj correction) and (rim with width))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 16:05
L26	18	L25 and segment	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 16:05
L27	7	L26 and ((reduc\$3 or downsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 16:05
S1	2	10/413052	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 14:28

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S2	1	10/658933	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 14:29
S3	3	09/746369	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:14
S4	1722	@rlad<"20001220" and (opc or (optical adj proximity adj correction) and (rim with width))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:17
S5	253	@rlad<"20001220" and simulat\$3 and (opc or (optical adj proximity adj correction) and (rim with width))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:07
S6	107	S5 and segment	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:34
S7	38	S6 and ((reduc\$3 or downsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:35
S8	4	S6 and ((enlarg\$3 or upsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:35
S9	3	@rlad<"20001220" and simulat\$3 and tri-tone and (phase-shift\$3 with mask) and (opc or (optical adj proximity adj correction) and (rim with width))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 13:26
S10	2	S9 and segment	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:23
S11	0	S10 and ((enlarg\$3 or upsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:23

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S12	2	S10 and ((reduc\$3 or downsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:23
S13	1	S7 and ((enlarg\$3 or upsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:25
S14	29	09/130996	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 15:25
S15	1	"6503666".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:02
S16	8	09/623195	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:30
S17	3	@rlad<"20001220" and simulat\$3 and tri-tone and (phase-shift\$3 with mask) and (opc or (optical adj proximity adj correction))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/24 12:49
S18	3	@rlad<"20001220" and simulat\$3 and tri-tone and (phase-shift\$3 with mask)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:32
S19	10	@rlad<"20001220" and simulat\$3 and tri-tone	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:33
S20	38	@rlad<"20001220" and simulat\$3 and (attenuat\$3 with phase-shift\$3 with mask) and (opc or (optical adj proximity adj correction) and (rim with width))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:34
S21	18	S20 and segment	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:34

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S22	7	S21 and ((reduc\$3 or downsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:35
S23	0	S22 and ((enlarg\$3 or upsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:35
S24	0	S21 and ((enlarg\$3 or upsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:35
S25	0	S20 and ((enlarg\$3 or upsiz\$3) with (region or area))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/05/23 16:35

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 Proceedings of SPIE are timely, high-quality proceedings of technical conferences on optics, imaging, and photonics. ... reduction, **optical proximity correction (OPC)**, and phase shift lithography techniques, **mask-related** ... so called **Tri-tone PSM**, we can ... of the pattern **layout** during the exposure ...
www.spie.org/web/abstracts/3200/3236.html - 117k - [Cached](#) - [More from this site](#) - [Save](#)
2. **Semiconductor International - Application of Chromeless Phase Lithography (CPL) Masks in ArF Lithography - 2/1/2003...** 
 The challenges of low-k1 lithography require unique solutions at all levels of the lithography process. ... techniques (RETs). **Optical proximity correction (OPC)** is currently ... 6, a **tri-tone** inspection problem will ... and **mask** build to the left. The far left image is the actual **layout** with ...
[reed-electronics.com/SEMICONDUCTOR/article/CA273501?pubdate=2/1/...](http://reed-electronics.com/SEMICONDUCTOR/article/CA273501?pubdate=2/1/2003) - [More from this site](#) - [Save](#)
3. **Search SPIE Papers - Publications - SPIE Web** 
 ... Enforcement of **Mask** Rule Compliance in Model-Based **OPC**'ed Layouts during ... Programmable RET **Mask Layout** Verification [4889-151 ... Advanced 193 **tri-tone** EAPSM (9%-18%) for 65 nm node ...
www.spie.org/app/publications/index.cfm?fuseaction=toc&volume=4889 - 83k - [Cached](#) - [More from this site](#) - [Save](#)
4. **SPIE Bookstore** 
 ... **OPC** to be performed on full chip **layout** ... **mask** pattern complexity through the elimination of optical enhancements such as phase shifting and **optical proximity correction** ... thin **tri-layer** ...
bookstore.spie.org/index.cfm?fuseaction=detailvolume&... - 197k - [Cached](#) - [More from this site](#) - [Save](#)
5. **EFFECTING FRONTAL RADIATION MODIFICATION DURING EXPOSURE, E.G., SCREENING, MASKING, STENCILING, ETC. - Patent Storm** 
 Patent Storm provides patent search capability of the US Patent Office patent information. Search for inventors and their inventions or browse the latest patents of their inventions. ... 7026081. **Optical proximity correction** method utilizing phase ... topography compensation at **mask** design: 3D **OPC** topography anchored ... as inputs to **mask layout** creation. Accurate predictions ...
patentstorm.us/class/430/396-EFFECTING_FRONTAL_RADIATION_MODIFICATI... - 48k - [Cached](#) - [More from this site](#) - [Save](#)
6. **acronymes** 
 Bonn Germany) BUS Broadcast and Unknown Server (LANE) BUT Board Under Test BV Bureau Veritaas BVBS BundesVereinigung der BauSoftwarehäuser (Germany) BVIT BundesVerband InformationsTechnologien (e.V. ... Package CDL Capacitance-Driven

Discrete Multi-Tone DMTF Desktop Management Task ... GA) GTS
Global Tri-State GUI Graphical User ...
www.ginko.de/user/franz.hamberger/acronyms.txt - 209k - [Cached](#) -
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7. [Structure and method of correcting proximity effects in a tri-tone attenuated phase-shifting mask - Patent 6653026](#)

... Unfortunately, a tri-tone phase-shifting mask exhibits strong ...
layout and tools in use). Steps 410-430 can be performed using any
optical proximity correction (OPC) tool (current OPC ...
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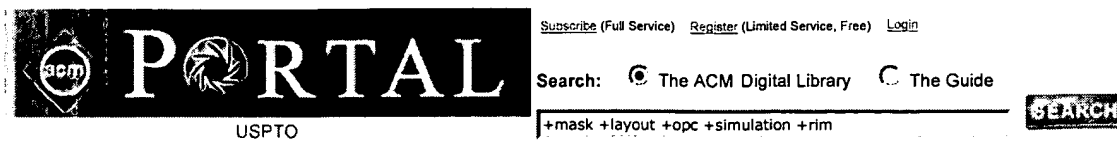
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1 [Subwavelength lithography and its potential impact on design and EDA](#)



Andrew B. Kahng, Y. C. Pati

June 1999

Proceedings of the 36th ACM/IEEE conference on Design automation

Publisher: ACM Press

Full text available: [pdf\(188.93 KB\)](#)Additional Information: [full citation](#), [references](#), [citations](#), [index terms](#)

2 [Subwavelength optical lithography: challenges and impact on physical design](#)



A. B. Kahng, Y. C. Pati

April 1999

Proceedings of the 1999 international symposium on Physical design

Publisher: ACM Press

Full text available: [pdf\(1.30 MB\)](#)Additional Information: [full citation](#), [references](#), [citations](#), [index terms](#)

3 [Fast Prolog with an extended general purpose architecture](#)



Bruce K. Holmer, Barton Sano, Michael Carlton, Peter Van Roy, Ralph Haygood, William R. Bush, Alvin M. Despain, Joan M. Pendleton, Tep Dobry

May 1990

ACM SIGARCH Computer Architecture News , Proceedings of the 17th annual international symposium on Computer Architecture ISCA '90, Volume 18 Issue 3a

Publisher: ACM Press

Full text available: [pdf\(1.19 MB\)](#)Additional Information: [full citation](#), [abstract](#), [references](#), [citations](#), [index terms](#)

Most Prolog machines have been based on specialized architectures. Our goal is to start with a general purpose architecture and determine a minimal set of extensions for high performance Prolog execution. We have developed both the architecture and optimizing compiler simultaneously, drawing on results of previous implementations. We find that most Prolog specific operations can be done satisfactorily in software; however, there is a crucial set of features that the architecture must support ...

4 [Filling and slotting: analysis and algorithms](#)



Andrew B. Kahng, Gabriel Robins, Anish Singh, Huijuan Wang, Alexander Zelikovsky

April 1998

Proceedings of the 1998 international symposium on Physical design

Publisher: ACM Press

Full text available: [pdf\(1.19 MB\)](#)Additional Information: [full citation](#), [abstract](#), [references](#), [citations](#), [index terms](#)

In very deep-submicron VLSI, certain manufacturing steps — notably optical exposure, resist development and etch, chemical vapor deposition and chemical-mechanical polishing (CMP) — have varying effects on device and interconnect features depending on local characteristics of the layout. To make these effects uniform and predictable, the layout itself must be made uniform with respect to certain density parameters. Traditionally, only foundries have performed the p ...



A methodology for modeling the effects of systematic within-die interconnect and device variation on circuit performance

Vikas Mehrotra, Shiou Lin Sam, Duane Boning, Anantha Chandrakasan, Rakesh Vallishayee, Sani Nassif

June 2000 **Proceedings of the 37th conference on Design automation**

Publisher: ACM Press

Full text available: pdf(1.01 MB)

Additional Information: [full citation](#), [abstract](#), [references](#), [citations](#), [index terms](#)

We present a methodology to study the impact of spatial pattern dependent variation on circuit performance and implement the technique in a CAD framework. We investigate the effects of interconnect CMP and poly CD device variation on interconnect delay and clock skew in both aluminum and copper interconnect technology. Our results indicate that interconnect CMP variation strongly affects interconnect delay, while poly CD variation has a large impact on clock skew in a 1 GHz design. Given th ...

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IEEE CNF IEEE Conference Proceeding

IEE CNF IEE Conference Proceeding

IEEE STD IEEE Standard

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IEEE CNF IEEE Conference Proceeding

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IEEE STD IEEE Standard

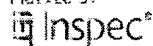
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